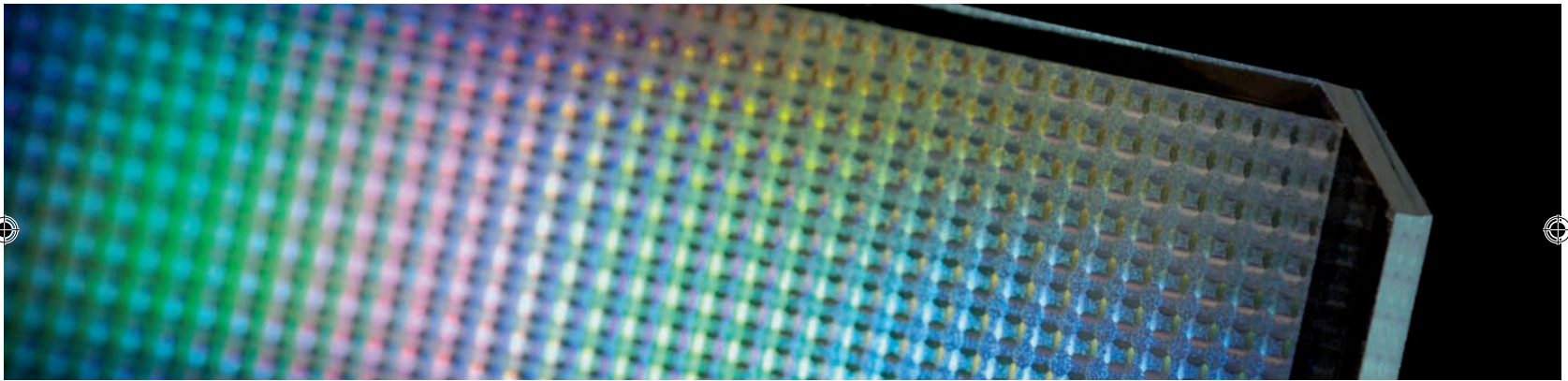




## Diffraction Optical Elements for off-axis Illumination



Multipole pupil illumination patterns are required to achieve the highest resolution in mask projection systems.

Diffraction Optical Elements (DOE) by Jenoptik efficiently generate such patterns with high precision and uniformity. The use of high-quality materials for the Jenoptik DOE results in high lifetime even under intense ultraviolet laser irradiation.

#### Features:

- Precise, homogeneous multipole illumination
- Arbitrary illumination patterns
- Highest efficiency by multilevel diffractive structures
- Cost-efficient binary DOE
- High damage threshold and lifetime
- Custom design with short delivery time.

#### Applications:

- Semiconductor lithography
- Laser materials processing
- Laser measuring systems

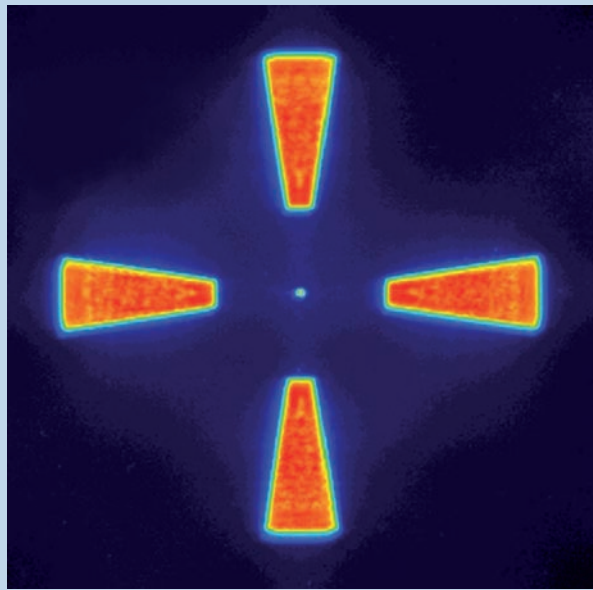
# Diffraction Optical Elements for off-axis Illumination

## Specifications

Wavelengths:	193 nm to 2.5 $\mu$ m
Max. efficiency:	94 % (multilevel)* / 78 % (binary)*
Max. N. A. (@ $\lambda = 193$ nm):	0.05 (multilevel) / 0.6 (binary)
Intensity profiles:	arbitrary geometries and profiles
Pole balance:	< 1 %
Pole uniformity:	< 5 %
Zero order:	< 0.1 % (multilevel) / < 0.25 % (binary)
Clear aperture:	< 120 mm x 120 mm
Materials:	UV grade Fused Silica, crystalline Quartz
AR-Coating:	On request
Product number:	029110

\* AR coated

False colour image of the far field intensity distribution of a Jenoptik DOE



It is our policy to constantly improve the design and specifications. Accordingly, the details represented herein cannot be regarded as final and binding.



JENOPTIK | Optical Systems  
Microoptics Business Unit  
JENOPTIK Laser, Optik, Systeme GmbH  
Goeschwitzer Strasse 25 | 07745 Jena | Germany  
Phone +49 3641 65-2442 | Fax -2443  
microoptics@jenoptik.com | www.jenoptik-los.com

MEMS Optical, Inc.  
205 Import Circle | Huntsville | AL 35806 | USA  
Phone +1 256 859-1886 | Fax +1 256 859-5890  
info@memsoptical.com | www.memsoptical.com

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